

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : 09/546,174 Confirmation No.: 4793
Applicant : Chih-Chien Liu
Filing Date : April 11, 2000
Title : HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION
PROCESS
Group Art Unit : 1796
Examiner : Sergent, Rabon A.
Docket No. : 20952.4002
Customer No. : 34313

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT IN RESPONSE TO FINAL OFFICE ACTION

Sir:

Applicants filed a Notice of Appeal on June 13, 2008 in response to the Final Office Action dated March 13, 2008, so that this amendment is timely filed. Please amend the above-identified application as follows:

Amendments to the claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 10 of this paper.